Claims

1 A plasma processing apparatus, comprising:

an evacuated chamber for containing a plasma,

a radio frequency source for exciting said plasma using radio
frequency energy, and

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a re-entrant vessel positioned within the chamber to shape and make more uniform said plasma contained within the chamber,

wherein the re-entrant vessel is movable within the chamber in at least a first direction to adjust the plasma uniformity, and the re-entrant vessel includes extensions of adjustable shape or position, which may be altered to further adjust and unify said plasma within said chamber.

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A plasma processing apparatus, comprising
 an evacuated chamber for containing a plasma,
 a radio frequency source for exciting said plasma using radio

 frequency energy,

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a re-entrant vessel, positioned within the chamber to shape and make more uniform said plasma contained within the chamber, and one or more magnets, positioned within the re-entrant vessel.

- 3. The apparatus of claim 2, further comprising an actuator for moving said magnets.
- 4. The apparatus of claim 1, further comprising a radio frequency emitting coil within said re-entrant vessel.
- 5. The apparatus of claim 1 or 2 wherein said re-entrant vessel is not evacuated.
 - 6. An ion optic grid, comprising

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a plate having first and second surfaces and defining a plurality of parallel apertures extending between said first and second surfaces, and tuning features incorporated into the plate, altering one of the surfaces and surrounding an aperture.

- 7. The ion optic grid of claim 6 wherein one said tuning feature reduces the diameter of the associated aperture.
- 8. The ion optic grid of claim 6 wherein one said tuning feature decreases or increases the length of the associated aperture.

9. A radio frequency coil for a plasma processing chamber, comprising,

a winding of an electrical conductor to be driven by an RF source, and

a flux concentrator positioned adjacent to the winding in at least one angular region thereof.